

<b>Notice of References Cited</b>		Application/Control No. 09/678,793	Applicant(s)/Patent Under Reexamination KANNO ET AL.	
		Examiner Lynette T. Umez-Eronini	Art Unit 1765	Page 1 of 1

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	M	US-			

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	N	JP-10319606-A	12-1998	Japan	Takahashi et al.	H01L 21/027
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**NON-PATENT DOCUMENTS**

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	U	Takahashi et al., Developer for Photoresist, December 4, 1998, Computer translation of JP 10319606 A (in English), 5 pages.
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\*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)  
Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.